

## **REMARKS**

### **Corrected Formal Drawings**

Applicant herewith submits corrected formal drawings for Figure 2 and Figure 3 (b) to match the informal drawings that were originally filed with the application. In Figure 2, a lower part of an element labeled with reference numeral 400 has been corrected to connect to another element labeled with reference numeral 330. Furthermore, in Figure 3 (b), reference numeral 300 has been corrected to 310. No new matter has been added.

Applicant herewith submits corrected formal drawings for Figure 1 (b) to match the specification that was originally filed with the application. In Figure 1 (b), reference numeral 105 has been corrected to 1105. Support is provided in paragraph 26 on page 8 of the specification. In addition, in Figure 1 (b), reference numeral 71 has been corrected to refer to an angle of exposure radiation (70) relative to a front surface of a reflective mask assembly (1050). Support is provided in paragraph 25 on page 7 of the specification. This is analogous to reference numeral 61 that refers to an angle of exposure radiation (60) relative to a front surface of a transmissive mask assembly (50), as shown in Figure 1 (a). No new matter has been added.

### **Claim Rejections 35 U.S.C. § 102 (e)**

The Examiner has rejected claims 1, 3-4, and 10 under 35 U.S.C. §102 (e) as being anticipated by Hsueh et al. (U.S. 6,569,576).

### Claims 1 and 3-4

Applicant has amended claim 1. Support is provided in paragraph 68 on page 17 of the specification.

Claim 1, as amended, of Applicant's claimed invention claims an apparatus including: a mask (100); a pellicle spacer (200), the pellicle spacer attached to the mask; and an electrostatic pellicle system (300) for attracting contaminants (500), the electrostatic pellicle system attached to the pellicle spacer. See Figure 1 (a), Figure 2, and Figure 3.

In contrast, the Hsueh et al. reference cited by the Examiner teaches a reticle (300) formed from a translucent quartz substrate with a glass side (302) on which are etched or deposited a first grid of conductive lines (301). Hsueh et al. further teaches that the reticle has opaque chrome mask patterns (305, 307, 308) deposited on the opposite side which are enclosed by a supporting frame (303) and covered by a transparent pellicle with a pellicle surface (304) on which are etched or deposited a second grid of conductive lines (306). See Figures 3-4. Also, see Col. 5, lines 24-59.

Hsueh et al. teaches that, in one aspect, the conductive lines may be sub-resolution wires. See Col. 4, lines 4-11. Also, see Col. 5, lines 7-16.

Hsueh et al. teaches that, in another aspect, the conductive lines may be outside the focal plane of the exposure tool reduction lens during the lithographic mask pattern transfer process. Col. 4, lines 12-22. Also, see Col. 5, lines 17-23.

Thus, the Hsueh et al. reference cited by the Examiner fails to teach an electrostatic pellicle system for attracting contaminants. Since Hsueh et al. fails to teach each and every element of Applicant's claimed invention, as claimed in claim 1, as amended, Hsueh et al. does not anticipate Applicant's claimed invention, as claimed in claim 1.

Claims 3-4 are dependent on claim 1. Since Hsueh et al. fails to teach each and every element of Applicant's claimed invention, as claimed in claim 1, as amended, Hsueh et al. also does not anticipate Applicant's claimed invention, as claimed in claims 3-4.

In view of the foregoing, Applicants respectfully request the Examiner to withdraw the rejections to claims 1 and 3-4 under 35 U.S.C. § 102 (e).

### **Claim 10**

Applicant has amended claim 10. Support is provided in paragraph 68 on page 17 of the specification.

Claim 10, as amended, of Applicant's claimed invention claims an apparatus including: a mask (1100); exposure radiation (70) incident on the mask; and an electrostatic pellicle system (300) for attracting contaminants (500) that is located between the mask and the exposure radiation. See Figure 1 (b), Figure 2, and Figure 3.

In contrast, the Hsueh et al. reference cited by the Examiner teaches a reticle (300) formed from a translucent quartz substrate with a glass side (302) on which are etched or deposited a first grid of conductive lines (301). Hsueh et al. further teaches that the reticle has opaque chrome mask patterns (305, 307, 308) deposited on the opposite side which are enclosed by a supporting frame (303) and protected by a transparent pellicle with a pellicle surface (304) on which are etched or deposited a second grid of conductive lines (306). See Figures 3-4. Also, see Col. 5, lines 24-59.

Hsueh et al. teaches that, in one aspect, the conductive lines may be sub-resolution wires. See Col. 4, lines 4-11. Also, see Col. 5, lines 7-16.

Hsueh et al. teaches that, in another aspect, the conductive lines may be outside the focal plane of the exposure tool reduction lens during the

lithographic mask pattern transfer process. Col. 4, lines 12-22. Also, see Col. 5, lines 17-23.

Thus, the Hsueh et al. reference cited by the Examiner fails to teach an electrostatic pellicle system for attracting contaminants. Since Hsueh et al. fails to teach each and every element of Applicant's claimed invention, as claimed in claim 10, as amended, Hsueh et al. does not anticipate Applicant's claimed invention, as claimed in claim 10.

In view of the foregoing, Applicants respectfully request the Examiner to withdraw the rejections to claim 10 under 35 U.S.C. § 102 (e).

### **Allowable Subject Matter**

The Examiner has stated that claims 2, 5-9, and 11-14 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Applicant has amended claim 1 to be allowable. Claims 2 and 5-9 are dependent on claim 1 and should also be allowable.

Applicant has amended claim 10 to be allowable. Claims 11-14 are dependent on claim 10 and should also be allowable.

### **Conclusion**

Applicant believes that all claims pending of Applicant's claimed invention, including amended claims 1 and 10, are now in condition for allowance so such action is earnestly solicited at the earliest possible date.


Should there be any additional charge, please charge Deposit Account No. 02-2666.

If a telephone interview would in any way expedite the prosecution of this application, the Examiner is invited to contact the undersigned at (408) 720-8300.

Respectfully submitted,

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